

ABSTRACT

SILICON-GERMANIUM HYDRIDES AND METHODS FOR MAKING AND USING SAME

The present invention provides silicon-germanium hydride compounds, methods for their synthesis, methods for their deposition, and semiconductor structures made using the compounds. The compounds are defined by formula : SiHn1 (GeHn2)y , wherein y is 2, 3, or 4 wherein n1 is 0, 1, 2 or 3 to satisfy valency and wherein n2 is independently 0, 1, 2 or 3 for each Ge atom in the compound, to satisfy valency.

Figure 1



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